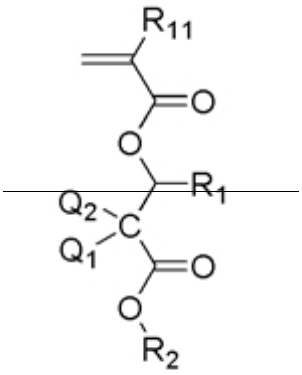
CLAIMS

~~1. A compound represented by the following formula (1):~~

~~[Formula 1]~~



~~wherein R_{11} represents any one selected from the group consisting of a hydrogen atom, a halogen atom, an alkyl group having 1to 8 carbon atoms, and a halogenated alkyl group having 1 to 5 carbon atoms;~~

~~R_1 represents any one selected from the group consisting of an alkyl group, a heteroalkyl group, an aryl group, a heteroaryl group, a cycloalkyl group, a heterocycloalkyl group, an alkyl ether group, and an alkylcarbonyl group;~~

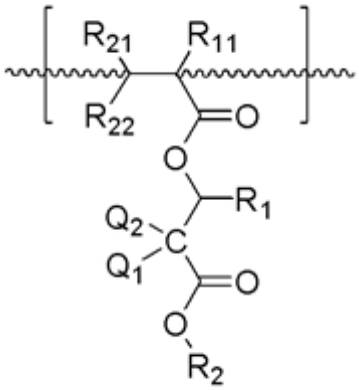
~~R_2 represents any one selected from the group consisting of a hydrogen atom and an alkyl group having 1 to 5 carbon atoms; and~~

~~Q_1 and Q_2 each independently represent any one selected from the group consisting of a hydrogen atom and a halogen atom.~~

~~2~~1. A resist protective film composition comprising a copolymer, wherein the copolymer ~~comprising~~ comprises a repeating unit represented by the following formula (1-a); and a repeating unit represented by any one selected from the group consisting of the following formula (4-a), formula (5-a), formula (6-a), formula (7-a), and combinations

thereof:

[Formula 1-a]



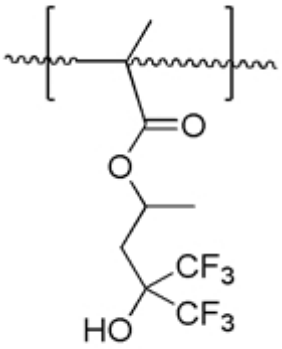
wherein R_{11}, R_{21} and R_{22} each independently represent any one selected from the group consisting of a hydrogen atom, a halogen atom, an alkyl group having 1 to 8 carbon atoms, and a halogenated alkyl group having 1 to 5 carbon atoms;

R_1 represents any one selected from the group consisting of an alkyl group, a heteroalkyl group, an aryl group, a heteroaryl group, a cycloalkyl group, a heterocycloalkyl group, an alkyl ether group, and an alkylcarbonyl group;

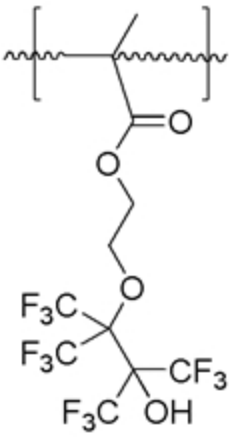
R_2 represents any one selected from the group consisting of a hydrogen atom and an alkyl group having 1 to 5 carbon atoms; and

Q_1 and Q_2 each independently represent ~~any one selected from the group consisting of a hydrogen atom and~~ a halogen atom;

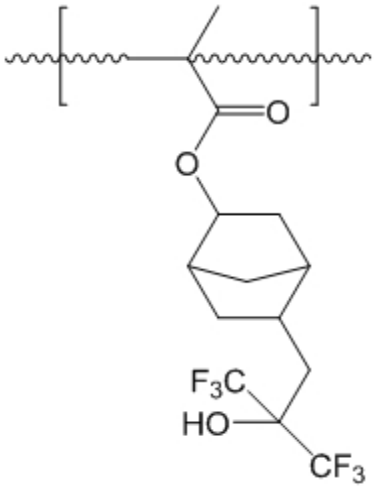
[Formula 4-a] [Formula 5-a]

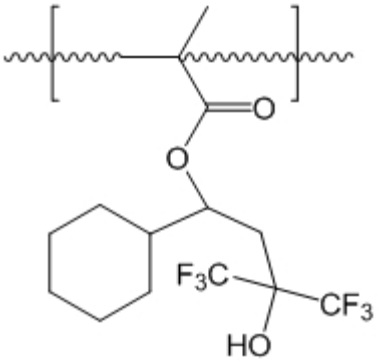


[Formula 6-a]



[Formula 7-a]

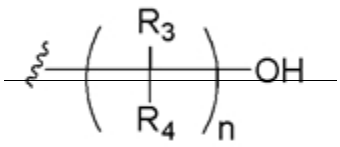




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~~3. The copolymer according to claim 2, further comprising a repeating unit containing a functional group represented by the following formula (2):~~

~~[Formula 2]~~



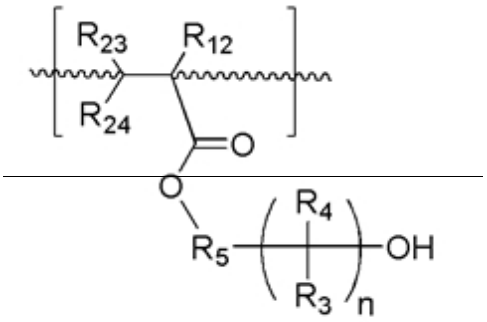
~~wherein R_3 and R_4 each independently represent any one selected from the group consisting of a hydrogen atom, an alkyl group having 1 to 10 carbon atoms, and a halogenated alkyl group having 1 to 10 carbon atoms;~~

~~any one selected from the group consisting of R_3, R_4 and a combination thereof is a halogenated alkyl group; and~~

~~n represents an integer from 1 to 6.~~

~~4. The copolymer according to claim 3, wherein the repeating unit containing a functional group represented by the formula (2) is a repeating unit represented by the following formula (3-a):~~

~~[Formula 3-a]~~



~~wherein R_{12}, R_{23} and R_{24} each independently represent any one selected from the group consisting of a hydrogen atom, a halogen atom, an alkyl group having 1 to 8 carbon atoms, and a halogenated alkyl group having 1 to 5 carbon atoms;~~

~~R_3 and R_4 each independently represent any one selected from the group consisting of a hydrogen atom, an alkyl group having 1 to 10 carbon atoms, and a halogenated alkyl group having 1 to 10 carbon atoms;~~

~~any one selected from the group consisting of R_3, R_4 and a combination thereof is a~~

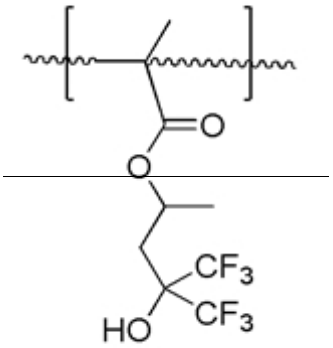
halogenated alkyl group;

R_5 represents a divalent hydrocarbon group; and

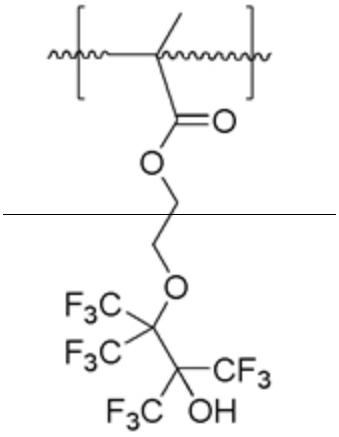
n represents an integer from 1 to 6.

5. The copolymer according to claim 4, wherein the repeating unit represented by the formula [3-a] is a repeating unit represented by any one selected from the group consisting of the following formula (4-a), formula (5-a), formula (6-a), formula (7-a), and combinations thereof:

[Formula 4-a]

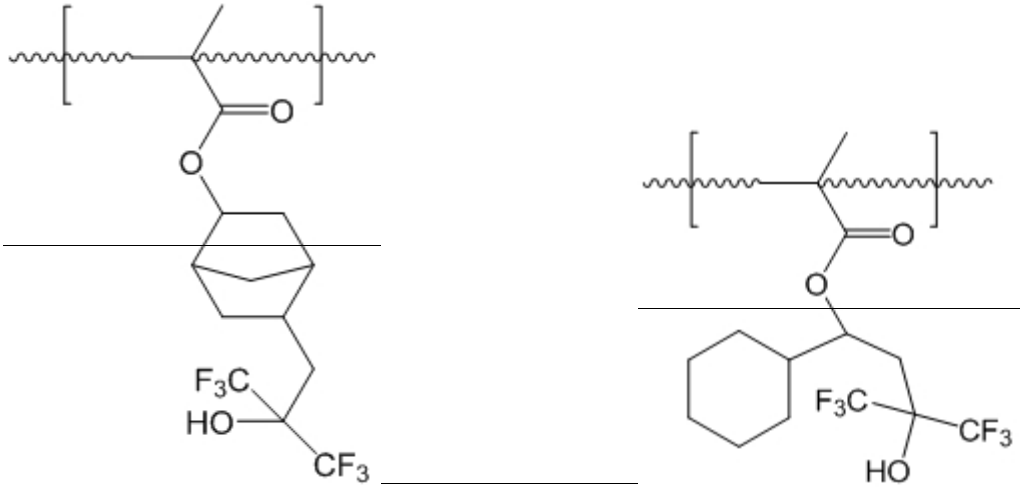


[Formula 5-a]



[Formula 6-a]

[Formula 7-a]



6~~2~~. The ~~copolymer~~ resist protective film composition according to claim ~~4~~1, wherein the molar proportion m of the repeating unit represented by the formula (1-a) is $0.01 \leq m \leq 0.6$, the molar proportion l of the repeating unit selected from the group consisting of the following formula (4-a), formula (5-a), formula (6-a), formula (7-a), and combinations thereof~~represented by the formula (3-a)~~ is $0.4 \leq l \leq 0.99$, and the sum of m and l is 1.

7~~3~~. The ~~copolymer~~ resist protective film composition according to claim ~~2~~1, wherein the copolymer has a weight average molecular weight as measured by gel permeation chromatography of 1,000 to 500,000 g/mol.

~~8. A resist protective film composition comprising the copolymer according to any one of claims 2 to 7.~~

9~~4~~. The resist protective film composition according to claim ~~8~~1, further comprising an alcohol solvent having 4 to 8 carbon atoms.